BJT Currents and HBTs

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7.4, 7.9 – Currents in the BJT, HBTs

HBT fabrication more complicated than slapping together p+np materials...

What is different than CMOS here? Think **R=ρL/A (Ω)**









2 Review

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Review this slide, and everything must make sense, else go back and <u>review part</u> <u>A of the previous lecture!</u>



Emitter (inject holes) Base (historical, Ge slab) Collector (collect holes) $|=|_E=|_B+|_C$



- (1) Holes injected do what?(2) Holes reach BC and do what?
- (3) Holes injected do what?
- (4) Electrons injected do what?
- (5) Electrons injected do what?
- (6) Reverse bias e or h do what? drift acro

diffuse across EB drift to C recombine with B electrons recombine with B holes diffuse across EB drift across BC (small)

Remember:

p+n for EB so (1) >> (5), $W_b \ll L_p$ so (2) >> (3), but (3) $\neq 0$

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3 🔳 Today's Goal

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- Goal today, calculate currents for the BJT
- Key Assumptions...

Holes diffuse from emitter to collector, drift is negligible (no *E-field* in B).

 $\gamma=1$... (i_F is all holes).

No collector reverse saturation current (6).

EB and BC junctions have the same area in one dimension (i.e. all horiz. current in diagram...).

All current and voltages steady state.



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Things will get VERY complicated, but hang on, I promise I will make them VERY simple in the end!



- Start with EB alone...
- Recall minority currents in a p+n junction (part of our p+np BJT).

$$\delta p(x_n) = \Delta p_n e^{-x_n/L_p}$$
$$\Delta p_n = p_n (e^{qV/kT} - 1)$$

Review,

The diagram at right is if V is positive...

If V=0 it will look like what?

If V is negative, will look like what?

The equation above predicts the answer! See the drawing I do at right during the video.





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Forward bias, diff dominates...

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note above is a logarithmic scale...



5 ■ The Case for p+np

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Note Fermi Levels shifts as voltage is applied...





Based on what we learned for the previous slide, where in the base, for the diagram at right should we see an excess of holes, or no (zero) holes at all?

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■ Carrier Flow in the Base..

▶ Apply diffusion equation in ★ the base... why?

$$\frac{d^2\delta p(x_n)}{dx_n^2} = \frac{\delta p(x_n)}{L_p^2}$$

general meaning of diffusion equation: smaller Lp, or larger Δp , results in more curvature (rate of change in slope, of the change in charge)...





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In Chapter 4 we assumed one of the constants (C_1) was zero since excess holes disappeared at long distance (x) into n-type slab. Common sense! Hole concentration can't go to infinity!

But... we cannot do that here since $W_b << L_p$... Hmm... next slide!

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Lets apply boundary conditions (this is easy!). We know concentrations at edges (see above) and we have this equation now:

 $\delta p(x_n) = C_1 e^{x_n/L_p} + C_2 e^{-x_n/L_p}$ $\delta p(x_n = 0) = C_1 + C_2 = \Delta p_E$ $\delta p(x_n = W_b) = C_1 e^{W_b/L_p} + C_2 e^{-W_b/L_p} = \Delta p_C$

• For most differential equations, you would be done now... but for BJTs is more complex...

► 2 Eq. and 2 Variables, ICBST solving for C₁, C₂ we get: $C_1 = \frac{\Delta p_C - \Delta p_E e^{-W_b/L_p}}{e^{W_b/L_p} - e^{-W_b/L_p}} \qquad C_2 = \frac{\Delta p_E e^{W_b/L_p} - \Delta p_C}{e^{W_b/L_p} - e^{-W_b/L_p}}$ SECS 2077 – Semiconductor Devices ©

 qV_{CB}

Fn

10 ■ Carrier Flow in the Base..

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 $\delta p(x_n) = C_1 e^{x_n/L_p} + C_2 e^{-x_n/L_p}$

 $\delta_{p}(x_{n})$

 $\Delta p_E >> p_n$

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Substitute newly found C₁, C₂ back in to:

The two parts of the equation add up to a ~linear (nearly) hole distribution in base region:



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▶ We know at x_n=W_b we have all I_C

 \blacktriangleright We now have an equation (δ_p) for hole density at each of these edges

► We can then solve for I_{Ep} and I_c using Eq. 4-22 from Ch. 4,

$$I_p(x_n) = -qAD_p \frac{d\delta p(x_n)}{dx_n}$$

What is this equation and what does it tell us?











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15 ■ Quick Review! – *Take a Break!*

How do you solve a differential equation? (Just tell me the four general steps).

The hole concentration across the base, what does it look like?

- Is zero everywhere.
- Is excess on the emitter-side and zero at the collector-side.
- Is zero on the emitter-side and excess at the collector-side.
- I am tired and am going to bed...

Current is driven from emitter into the base by: drift, diffusion, neither, both.

• Current is driven across the base by: *drift, diffusion, neither,* both.

Current is driven from base into the collector by: drift, diffusion, neither, both.

Lastly, peak ahead, notice how in the equations we derived, they all share a blue-highlighted term such that all current increase or decrease at the SAME rate (but are obviously not equal). You should have expected this already based on what





• Remember, this is the equation for $\Delta p_E (V_{EB})$ but what does this mean?

 $\Delta p_E = p_n (e^{qV_{EB}/kT} - 1) \quad \mathbf{V}_{\mathsf{EB}} \bigstar \quad \mathbf{I}_{\mathsf{Ep}} \& \mathbf{I}_{\mathsf{C}} \& \mathbf{I}_{\mathsf{B}} \bigstar$

But what is the other 'stuff'

They ALL INCREASE the same with V_{EB} , diode forward bias, which makes perfect sense!

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 $qA\frac{\mathcal{L}_p}{L}p_n$

$$\Delta p_E = p_n (e^{qV_{EB}/kT} - 1)$$

$$I_{Ep} \approx qA\frac{D_p}{L_p}\Delta p_E \operatorname{ctnh}\frac{W_b}{L_p}$$

$$I_C \approx qA\frac{D_p}{L_p}\Delta p_E \operatorname{csch}\frac{W_b}{L_p}$$

$$I_B \approx qA\frac{D_p}{L_p}\Delta p_E \operatorname{tanh}\frac{W_b}{2L_p}$$

• How about this term in front? Steal the p_n from Δp_E ... recognize it?



is p+n diode, and also that is the whole point of why we derived these by solving the diff. eq. in the base only!

... this is getting simpler!

... <u>last thing we need</u> is a way to differentiate between the three components...



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Lastly, what do these hyperbolic trig functions do?

 $\frac{W_b}{L_p} \approx 0.1$ to 0.001 $e^{0.01} = 1.01$

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Remember, we want Wb smaller than Lp for good design (so holes get across without recombining)!

Example 7-4 in book:

$$N_D = 10^{15}/cc$$

 $L_P = 108 \ \mu m$
 $W_B = 1 \ \mu m$
 $\beta = 832$

19 ■ BJT Terminal Currents

$$\Delta p_E = p_n (e^{qV_{EB}/kT} - 1)$$

$$I_{Ep} \approx qA \frac{D_p}{L_p} \Delta p_E \operatorname{ctnh} \frac{W_b}{L_p}$$
$$I_C \approx qA \frac{D_p}{L_p} \Delta p_E \operatorname{csch} \frac{W_b}{L_p}$$
$$I_B \approx qA \frac{D_p}{L_p} \Delta p_E \operatorname{tanh} \frac{W_b}{2L_p}$$

Review 'parts' one last time...

Reverse sat. current (constant)!

Effect of V_{EB}! ALL scale together!

Current magnitudes must be different, and the effect of W_b and $L_p!$

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• To simplify our calculations we assumed $\delta = 1$ (which is a safe assumption).

▶ However, if you are a designer, you know in practice it is not unity, and would like to know how to get it as close to unity as possible...

 $\gamma = \frac{I_{Ep}}{i_{En} + i_{Ep}}$ $\gamma = \left[1 + \frac{L_p^n n_n \mu_n^p}{L_n^p p_p \mu_p^n} \tanh \frac{W_b}{L_p^n}\right]^{-1} \approx \left[1 + \frac{W_b n_n \mu_n^p}{L_n^p p_p \mu_p^n}\right]^{-1}$

 L_p^n = hole diffusion length in n-type base μ_n^p = electron mobility in p-type emitter

Also base transport should be as close to unity as possible for good design $i_c = Bi_{Ep}$

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 $\operatorname{sech}(z) = 1/\cosh(z)$

 $B = \frac{I_C}{I_E} = \frac{qA\frac{D_p}{L_p}\Delta p_E \operatorname{csch} W_b/L_p}{qA\frac{D_p}{L_p}\Delta p_E \operatorname{ctnh} W_b/L_p} = \operatorname{sech} \frac{W_b}{L_p}$

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▶ It should be noted that the highest performance BJTs are Heterojunction BTs (HBTs) using a wider-band-gap material for the emitter, why?



23 ■ Review!

► To get the current equations, we solved for what in the base? <u>Drift current equation, or diffusion current equation, neither, or both?</u>

▶ For our equations, what is the yellow? How does it effect currents as voltage changes?

► Is it good that all currents respond linearly to base current? <u>Not that I can think of, or wow I now have a single</u> <u>device that linearly amplifies current!</u>

▶ For our equations, what is the blue? <u>Hint, the BJT is just</u> <u>diodes, and this is a key part of the diode equation...</u>

► For our equations, what is the pink? How does it effect currents? <u>Hint, I need these, without these would I still have an amplifier?</u>

If we made W_b really large, what would our circuit and equations reduce to? <u>You can do the math, but to make this</u> <u>easier just trust your instincts, if Wb becomes large, you</u> <u>basically get two separate diodes, not a BJT. Does that give</u> <u>you amplification then?</u>

Why do we make HBTs? <u>Improves emitter injection</u> <u>efficiency, but how?</u>



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▶ If time allows, let's run through an example HBT fabrication process...

An InP-Based Optoelectronic Integrated Circuit for Optical Communication Systems

Master of Science in Electrical Engineering Research Thesis

Shraga Kraus Submitted to the Senate of the Technion - Israel Institute of Technology Iyar 5766 Haifa May 2006



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Figure 2.12: Wafer layers after base etch







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Figure 2.14: Wafer layers after collector metal implementation

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Figure 2.15: Wafer layers after subcollector etch



Figure 2.16: Wafer layers after transistor passivation. Only emitter via is shown in this cross–section





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(a)



(c)











(a)



Instructor - Prof. Jason Heikenfeld



Figure 2.20: SEM images of a transistor and circuit at various fabrication process steps: (a) base–collector via (b) metal 1 deposition and liftoff (c) completed capacitor (d) completed interconnects with crossovers and a resistor

Figure 2.19: SEM images of a transistor at various fabrication process steps: (a) emitter etch (b) base metal deposition and liftoff (c) emitter protect (d) collector protect (e) isolation (f) emitter expose

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■ 28 ■ Testing!



Figure 2.46: Ebers-Moll model (injection version)

- Amplification factor is 15 mA/200 µA= 75
- We will talk about the circuit model above next time... looks simple right?



Figure 2.21: DC measurement setup: (a) measurement system (b) handmade probes





Figure 2.23: Common emitter measurement curves (measured on a large area device). I_B varies from 0 to 200 μ A in 20 μ A steps cenfeld